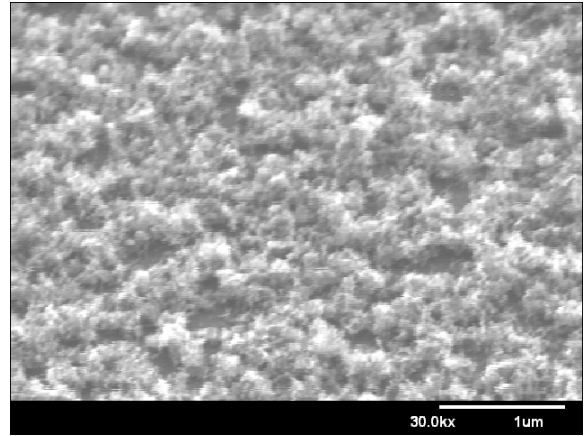
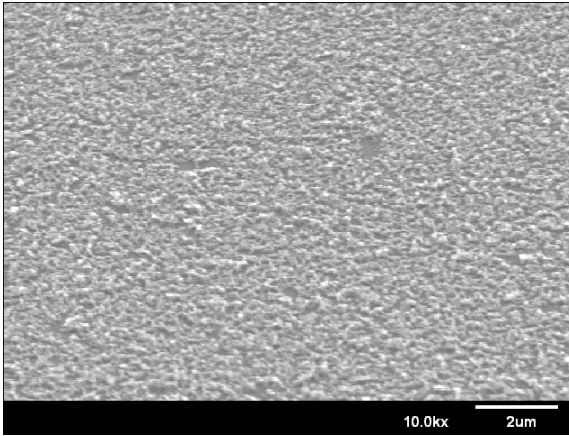
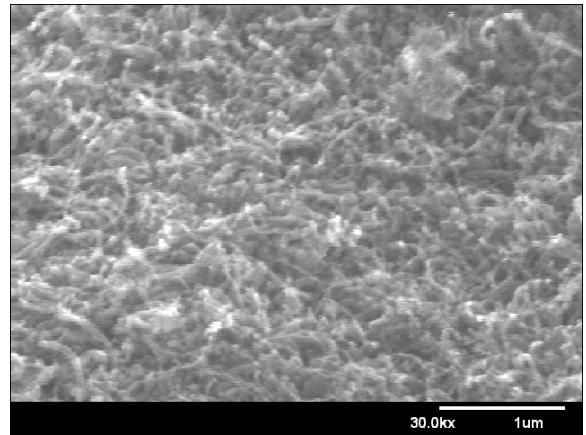
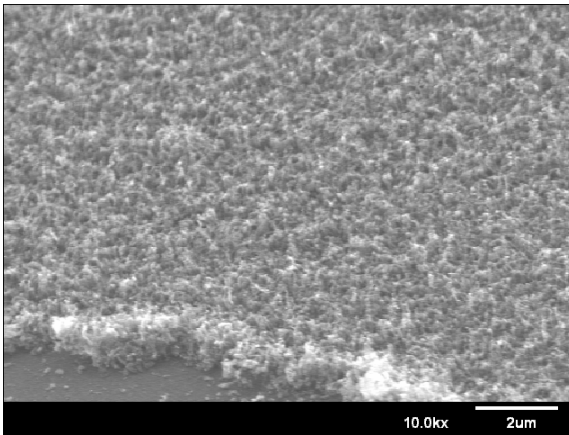


A3、550°C H₂:100 (Ni 7 nm)



A4、550°C H₂:100 (Ni 7 / TiN 20 nm)



A5、550°C H₂:100 (Ni 7 / TaN 10 nm)

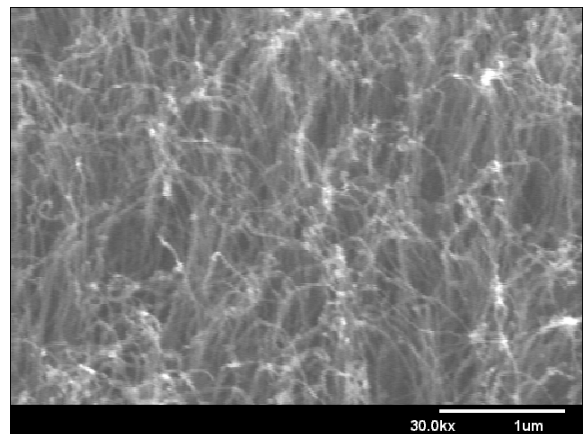
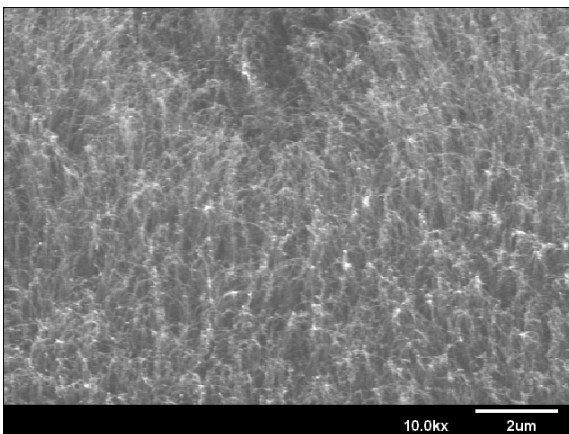
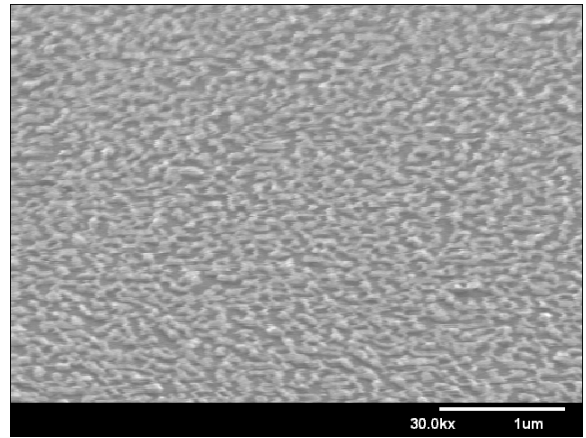
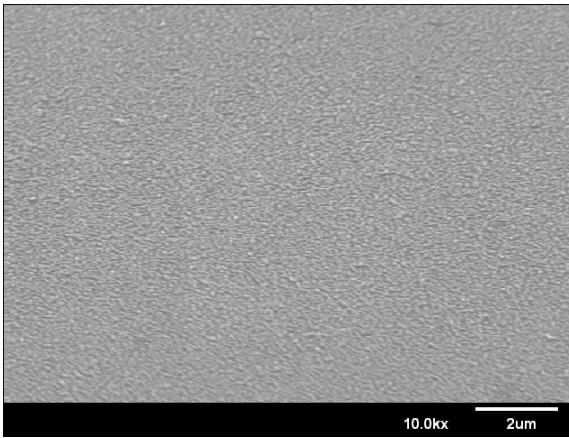
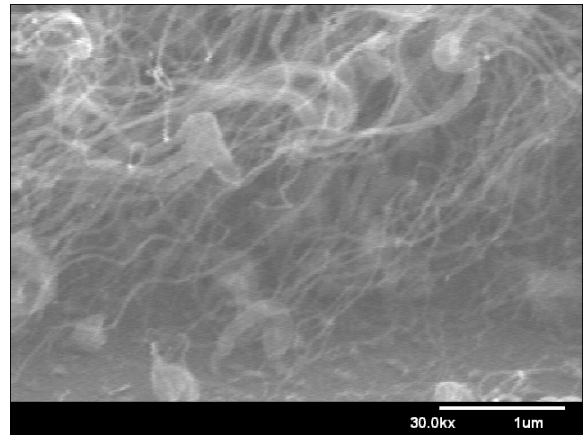
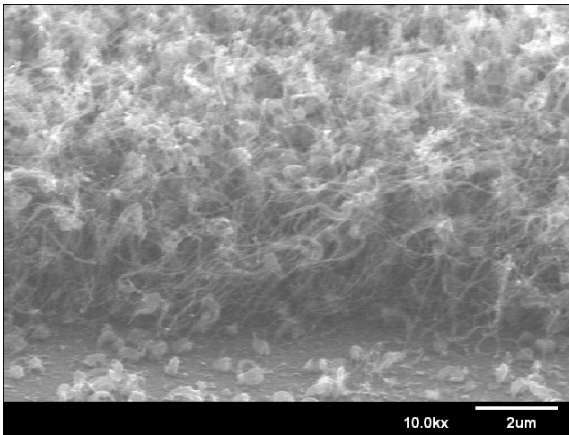


圖 4-29 製程 A 有緩衝層對照組試件(4、5) 奈米碳管 SEM 圖面(10、30 kx)

B3、550°C H₂:200 (Ni 7 nm)



B4、550°C H₂:200 (Ni 7 / TiN 20 nm)



B5、550°C H₂:200 (Ni 7 / TaN 10 nm)

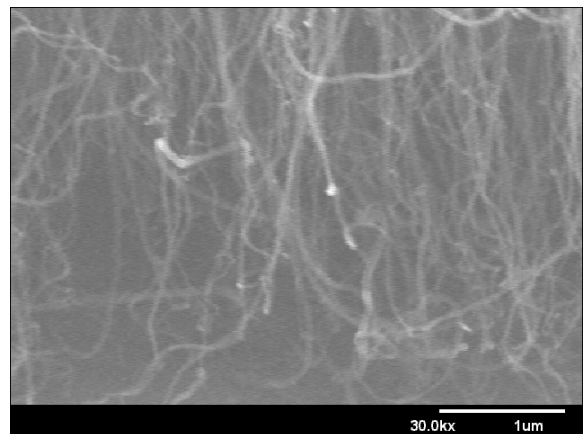
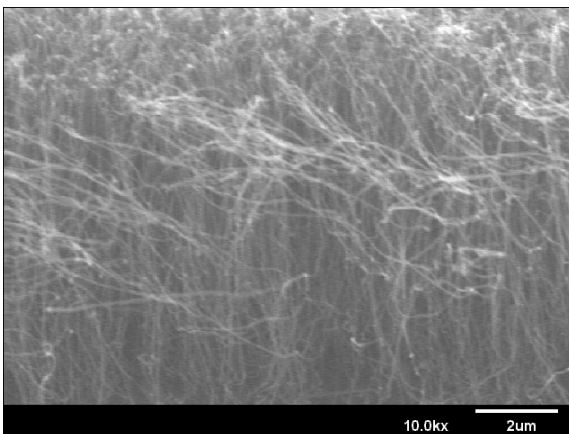


圖 4-30 製程 B 有緩衝層對照組試件(4、5) 奈米碳管 SEM 圖面(10、30 kx)